



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Chang Guo and Stephen Moffatt

Examiner:

Title: METHODS FOR FABRICATING
LITHOGRAPHY APPARATUS

Group Art:

Serial No.:

Filed: October 27, 2000

#2
P.G.
2-27-01

Director of Patents and Trademarks
Washington, D. C. 20231

INFORMATION DISCLOSURE STATEMENT

Sir:

Applicant respectfully requests that the following references be considered in the examination of the above-identified application. A copy of each reference is enclosed.

Cited Art

Article entitled "New approach to projection-electron lithography with demonstrated 0.1 um linewidth" by S.D. Berger et al., Applied Physics Letters, 57 (2), July 1990, pages 153-155.

Article entitled "Projection electron-beam lithography: A new approach", by S.D. Berger et al., J. Vac. Sci. Technol. B 9 (6), Nov/Dec 1991, pages 2996-2999.

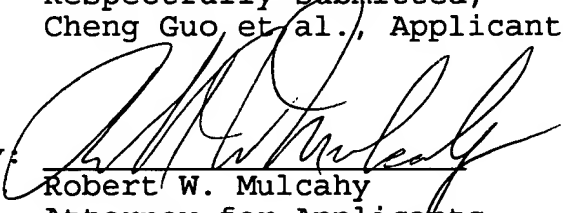
REMARKS

Under rule 37 C.F.R. 1.98(a), which is effective as of march 16, 1992, applicants subit that no specific comments are necessary for any of the above cited english language publications.

For the Examiner's convenience, applicants have attached a completed Form PTO-1449 hereto.

Respectfully submitted,
Cheng Guo et al., Applicants

By:


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